

Approved for
entry
12/30/03
HN

Marked-Up Substitute Specification

Application No. 09/986,958

TITLE OF THE INVENTION

**EXPOSURE APPARATUS, METHOD OF MANUFACTURING
SEMICONDUCTOR DEVICES, SEMICONDUCTOR MANUFACTURING
PLANT, METHOD OF MAINTAINING EXPOSURE APPARATUS, AND
POSITION DETECTOR**

FIELD OF THE INVENTION

This invention relates to an exposure apparatus and, more particularly, to an exposure apparatus used when a semiconductor device or the like is manufactured in a photolithography process.

BACKGROUND OF THE INVENTION

A demagnifying projection exposure apparatus is used widely in the fabrication of semiconductor circuits such as LSI chips. A demagnifying projection exposure apparatus